SUBSTRATE PROCESSING SYSTEM, SUBSTRATE PROCESSING APPARATUS, METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE, AND PROGRAM

ABSTRACT

There is provided a technique, which includes: at least one substrate processing apparatus including a controller configured to be capable of controlling processing of a substrate according to a recipe including at least one step and a first memory configured to be capable of storing data of the at least one substrate processing apparatus that is reported during the processing of the substrate; and a data manager connected to the at least one substrate processing apparatus, configured to acquire the data, and configured to be capable of specifying the number of the at least one step that is included in the data to be acquired such that the data falls within a predefined data acquirable range.

Fig. 5